

Refine Search

Search Results -

Terms	Documents
20020028636 or 20040040217 or 5116535.pn. or 5246624.pn. or 6248144.pn. or 6352679.pn. or 5904159.pn.	7

Database:

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 EPO Abstracts Database
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 Derwent World Patents Index
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Search:

L4

Search History

DATE: Monday, October 01, 2007
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Set Name	Query	Hit Count	Set Name
side by side			
DB=PGPB,USPT; PLUR=YES; OP=ADJ			
<u>L4</u>	20020028636 or 20040040217 or 5116535.pn. or 5246624.pn. or 6248144.pn. or 6352679.pn. or 5904159.pn.	7	<u>L4</u>
<u>L3</u>	(acid or acidic) near4 silica and (polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (basic or alkali) solution	32	<u>L3</u>
DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ			
<u>L2</u>	L1 and (acid or acedic) fumed silica	1	<u>L2</u>
<u>L1</u>	(polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (abrasive or silica or silicon dioxide or silicon oxide or (polishing or planarizing or planarization or cmp) (particle or particulate or grit or grain)) with (volume or vol or "vol." or "vol.%" of "vol%") with (size or diameter) with (nm or nanometer)	68	<u>L1</u>

END OF SEARCH HISTORY